

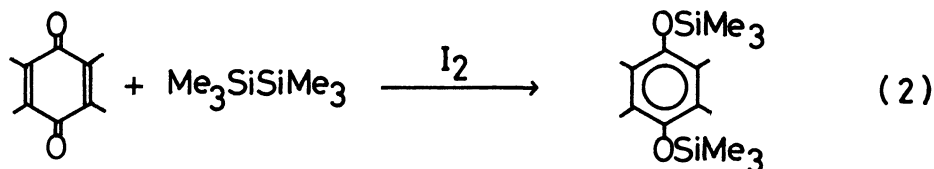
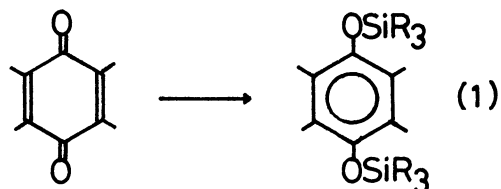
A NEW REDUCTIVE SILYLATION OF p-QUINONES WITH HEXAMETHYLDISILANE
CATALYZED BY IODINE

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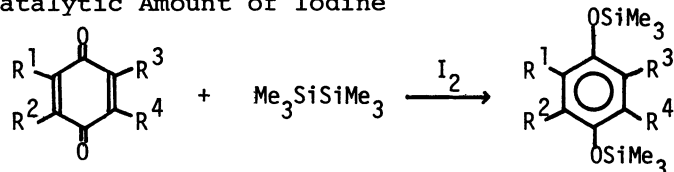
In the presence of a catalytic amount of iodine, hexamethyl-
disilane can reductively silylate p-quinones under mild conditions
to afford 1,4-bis(trimethylsiloxy)arenes in high yields.

Reductive silylation of type 1 may be an attracting method for protecting the
quinone fragment which is widely found in
natural products, since the resulting
bis(silyl)arenes can be readily converted
to their parent quinones.¹⁾ Nevertheless,
only scattered reports have appeared
concerning the silylation of quinones.
Thus, Bouas-Laurent and coworkers
reported the silylation of several p-
quinones with $\text{Me}_3\text{SiCl}/\text{Mg}$ to give the corresponding 1,4-bis(trimethylsiloxy)arenes
in 30-94% yields.²⁾ Also, Tsutsumi and coworkers treated p-benzoquinone with
 $\text{Me}_3\text{SiCl}/\text{K}$ to obtain the silylated product in 28% yield.³⁾ These conventional
silylations are generally accompanied by the concurrent formation of a large amount
of inorganic salts. Further, bis(trimethylsilyl)mercury has been reported by
Eaborn and coworkers⁴⁾ and Neumann and Neumann⁵⁾ to be an effective reagent for the
silylation of p-quinones (44-63%). Moreover, Kumada and coworkers have reported
that 1,2-difluorotetramethyldisilane reacted at 100°C in the presence of a
palladium catalyst with p-benzoquinone to afford the bis(silyl)benzene in 41%
yield.⁶⁾ The utility of reaction 1 has led us to explore the reductive silyla-
tion of a newer type. We now report our finding that, in the presence of a
catalytic amount of iodine, hexamethyldisilane silylates effectively p-quinones
(eqn. 2).



The reductive silylation can be simply performed by heating a benzene solution
of a binary mixture of quinone (1 equiv) and hexamethyldisilane (1.5 equiv) in the
presence of iodine (0.02 equiv). Results are summarized in Table 1, and it will
be seen from the Table that the reductive silylation proceeds very smoothly at
temperatures of 60-80°C to afford 1,4-bis(trimethylsiloxy)arenes in over 85% yield.

Table 1. Reductive Silylation of *p*-Quinones with Hexamethyldisilane in the Presence of a Catalytic Amount of Iodine^a



Run	R ¹	R ²	R ³	R ⁴	Conditions	Yield, % ^{b,c}
1	H	H	H	H	60°C, 3 h	99
2	Me	H	H	H	60°C, 3 h	91
3	Me	H	H	Me	60°C, 7 h	100
4	Me	Me	Me	Me	60°C, 12 h	86
5	Cl	H	H	Cl	80°C, 7 h	85
6	CH=CHCH=CH		H	H	60°C, 3 h	96
7	CH=CHCH=CH		H	Me	60°C, 5 h	95

^a[Quinone]/[disilane]/[I₂] = 1/1.5/0.02. Solvent = benzene.

^bDetermined by GLC. ^cAll the silylated products showed the expected IR, NMR, and Mass spectra for the structures assigned.

A typical procedure is as follows: a mixture of 1.39 g (10.1 mmol) of 2,5-dimethyl-*p*-benzoquinone, 2.18 g (14.8 mmol) of hexamethyldisilane, 0.059 g (0.23 mmol) of iodine, and 10 ml of benzene was stirred at 60°C under nitrogen. After 7 h, GLC analysis showed that the reaction had produced 1,4-bis(trimethylsilyloxy)-2,5-dimethylbenzene in quantitative yield. The IR and NMR spectra of the product were in good agreement with literature.¹⁾

The present silylation has advantages of simplicity of the reaction procedure, high yield of the products, and ready availability of the silylating agent. Work is in progress to extend the synthetic scope and to study on the mechanistic aspect.

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